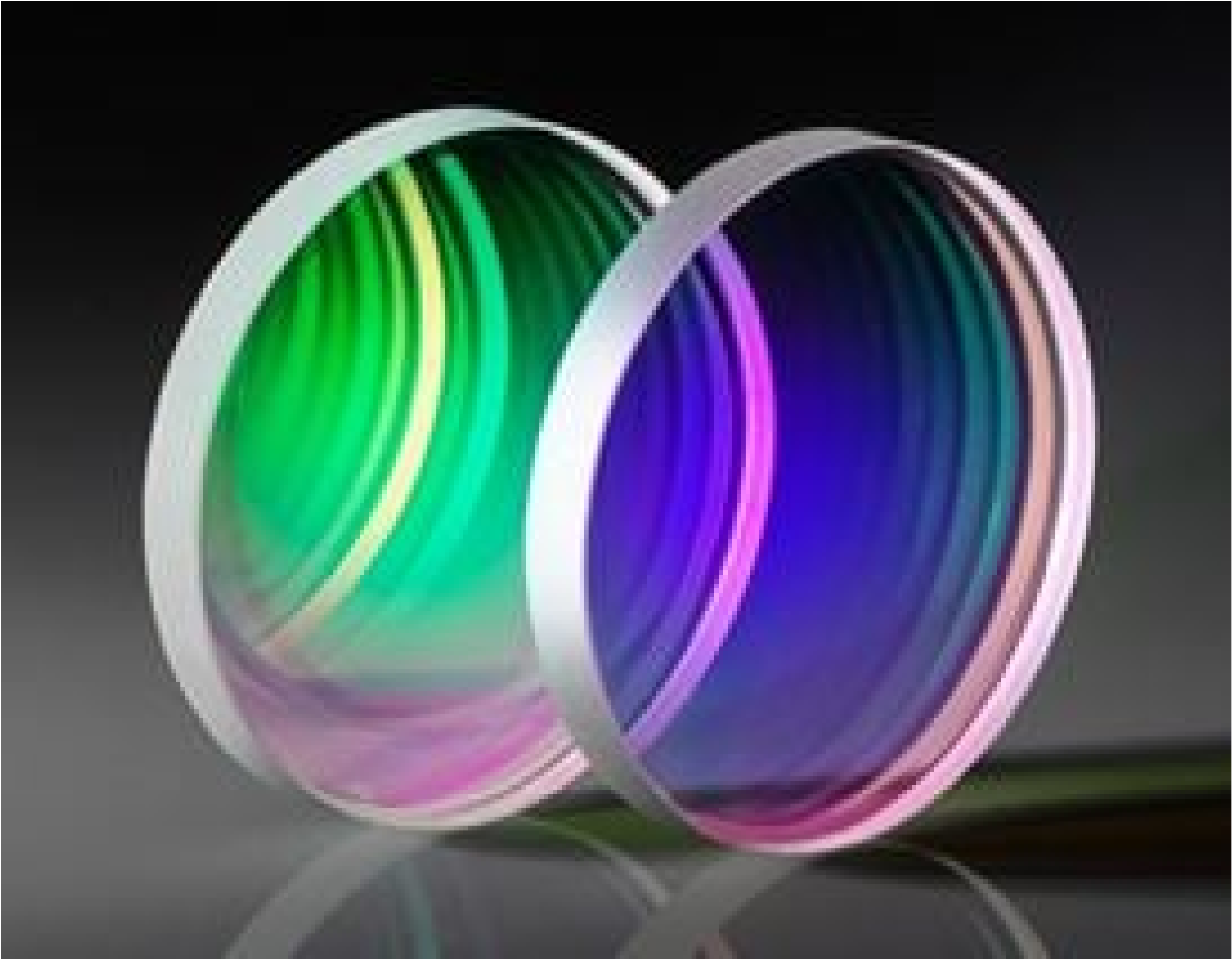


20-40nm, 50.8mm Dia, EUV/IR Dichroic Filter



Extreme Ultraviolet (EUV) Dichroic Filters

Stock **#18-280** **5 In Stock**

-

1

+

€5.400⁰⁰

ADD TO CART

Volume Pricing	
Qty 1+	€5.400,00 each
Need More?	Request Quote

i Prices shown are exclusive of VAT/local taxes

Product Downloads

General	
Dichroic Filter	Type:
Physical & Mechanical Properties	
50.80	Diameter (mm):
5.08 ±0.1	Thickness (mm):
	Parallelism (arcmin):

<5	
	Dimensional Tolerance (mm):
+0.0/-0.2	
Optical Properties	
	Angle of Incidence (°):
78	
Fused Silica (Corning 7980)	Substrate: □
Dielectric Multilayer AR	Coating:
	Reflection (%):
>40	
20-10	Surface Quality:
	Wavelength Range (nm):
20 - 40	
<λ/10 @ 633nm	Surface Figure, RMS:
Regulatory Compliance	
	Certificate of Conformance:
View	

Product Details

- Separates EUV from the NIR Laser Source in High Harmonic Generation
- Designed for High Damage Thresholds
- Supports Applications from 10 – 40nm
- Available from Stock
- No Minimum Order Quantities, No Coating Lot Charges

Extreme Ultraviolet (EUV) Dichroic Filters, also known as beam separators, are intended for high harmonic generation applications by providing a high separation efficiency between the EUV and NIR wavelengths. Featuring a Fused Silica substrate, these filters support higher laser powers than the alternative Brewster's angle beam separators and EUV filters. EUV Dichroic Filters feature a broad bandwidth range from 10nm to 40nm. In addition to high harmonic generation, these filters can also be used in systems that support EUV applications such as EUV lithography, EUV nanomachining, coherent diffractive imaging, and ultrafast attosecond pulse generation.